CLAIMS

1. A method of producing a conductive layer (5) on a substrate (1), comprising the steps of:

defining a groove (3) for the conductive layer (5) using a photodefinable insulator material (2); and

filling the groove (3) with a material capable of forming the conductive layer (5).

2. A method according to claim 1, wherein the step of defining the groove (3) comprises:

depositing the insulator material (2) onto the substrate (1);

defining a pattern in the insulator material; and

processing the pattern to form the groove (3).

3. A method according to claim 1 or 2, comprising filling the groove (3) using a blading technique.

4. A method according to any one of the preceding claims, wherein the material capable of forming the conductive layer (5) comprises a metal precursor.

5. A method according to any one of claims 1 to 3, wherein the material capable of forming the conductive layer (5) comprises a conductive ink.

6. A method according to claim 4 or 5, further comprising curing the material to obtain the conductive layer (5).

7. A method according to claim 6, further comprising etching the insulator material to reduce its thickness relative to the thickness of the conductive layer.

8. A method according to claim 6 or 7, comprising depositing one or more further functional layers over the conductive layer.

9. A method according to any one of the preceding claims, wherein the conductive layer comprises a row or column line in an active matrix liquid crystal display.

10. An active matrix liquid crystal display including a conductive layer made by a method according to any one of the preceding claims.

11. A device comprising a substrate (1) overlaid with a photodefinable insulator material (2), the material having a groove (3) for a conductive layer (5) defined therein.

12. A device according to claim 11, further comprising a conductive layer (5) in the groove (3).

13. A device according to claim 11 or 12, comprising an active matrix liquid crystal display.

14. A method of producing a conductive layer (5) on a substrate (1), comprising the steps of:

defining a groove (3) for the conductive layer (5); and

blading a material capable of forming the conductive layer (5) into the groove.

15. A method according to claim 14, comprising defining the groove (3) by printing an insulating material onto the substrate.

16. A method according to claim 14, wherein the step of defining the groove (3) includes depositing a material (2) onto the substrate (1) and defining the groove (3) in the material.

17. A method according to claim 16, wherein the material (2) comprises a photodefinable material.

18. A method according to any one of claims 14 to 17, wherein the substrate comprises a substrate for use in an active matrix liquid crystal display.

19. A method of producing a conductive layer (5) on a substrate for an active matrix liquid crystal display, the method comprising the steps of printing an insulating material (10) onto the substrate (1) such that the printed material defines a groove (3) for the conductive layer and filling the groove with a material capable of forming the conductive layer (5).